

Erratum to: Studies of electrical resistivity and magnetic properties of nanocrystalline CoFeCu thin films electrodeposited from citrate-added baths

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Due to a miscalculation, there was a mistake in Fig. 5 of the original publication. The correct version of Fig. 5 should be as shown below.

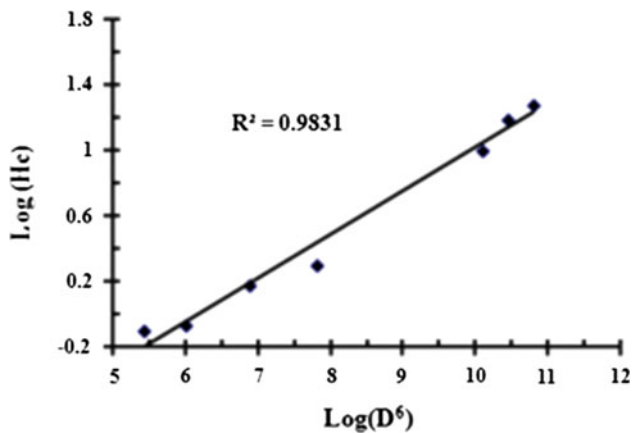


Fig. 5 D^6 -dependence of coercivity of CoFeCu thin films deposited from Table 1

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